CLAIMS

1. A server for use in performing digital lithography, the server comprising:

a memory comprising a virtual mask file, the virtual mask file including data defining elements that form one or more polygons; and

a controller coupled to the memory, the controller configured to:

receive data defining a table, the table including instructions to edit the elements of the virtual mask file; and

activate, deactivate, shift, or replace the elements according to the table to create an edited virtual mask file;

wherein the server is operable to be used in performing digital lithography on a substrate based on the edited virtual mask file.

2. The server of claim 1, wherein the edited virtual mask file includes at least one of the elements.

3. The server of claim 1, wherein the virtual mask file includes a mask pattern.

4. The server of claim 1, wherein the server further includes a rasterizer and a GPU.

5. The server of claim 1, wherein the table is formed from a defect list provided from a metrology tool coupled to the server.

6. The server of claim 1, wherein the virtual mask file includes layers of the elements.

7. The server of claim 1, wherein the virtual mask file includes arrays of the elements.

8. The server of claim 7, wherein the elements include a pixel cell, a bezel cell, a contact cell, an indium tin oxide (ITO) cell, or a display cell.

9. A method, comprising:

loading a virtual mask file into a memory of a server of a maskless lithography device, the virtual mask file including data defining elements that form one or more polygons;

sending data defining a table to the server, the table including instructions to edit the elements of the virtual mask file; and

activating, deactivating, shifting, or replacing the elements according to the table to create an edited virtual mask file, the edited virtual mask file created in the server of the maskless lithography device.

10. The method of claim 9, wherein the edited virtual mask file includes at least one of the elements.

11. The method of claim 9, wherein the virtual mask file includes a mask pattern.

12. The method of claim 9, wherein the server further includes a rasterizer and a GPU.

13. The method of claim 9, wherein the elements of the virtual mask file are overlapped.

14. The method of claim 9, wherein the virtual mask file includes layers of the elements.

15. The method of claim 9, wherein the virtual mask file includes arrays of the elements.

16. The method of claim 15, wherein the elements include a pixel cell, a bezel cell, a contact cell, an indium tin oxide (ITO) cell, or a display cell.

17. The method of claim 19, further comprising sending the edited virtual mask file to a processing unit of the maskless lithography device.

18. A non-transitory computer-readable medium storing instructions that, when executed by a processor, cause a computer system to perform the operations of:

loading a virtual mask file into a memory of a server of a maskless lithography device, the virtual mask file including data defining elements that form one or more polygons;

sending data defining a table to the server, the table including instructions to edit the elements of the virtual mask file; and

activating, deactivating, shifting, or replacing the elements according to the table to create an edited virtual mask file, the edited virtual mask file created in the server of the maskless lithography device.

19. The non-transitory computer-readable medium of claim 18, wherein the virtual mask file includes arrays of the elements.

20. The non-transitory computer-readable medium of claim 19, wherein the elements include a pixel cell, a bezel cell, a contact cell, an indium tin oxide (ITO) cell, or a display cell.